

Title (en)

DEVICE FOR GAS SEPARATION AND METHOD FOR PRODUCING ONE SUCH DEVICE

Title (de)

VORRICHTUNG ZUR GASSEPARATION SOWIE VERFAHREN ZUR HERSTELLUNG EINER SOLCHEN VORRICHTUNG

Title (fr)

DISPOSITIF DE SEPARATION DE GAZ ET PROCEDE POUR PRODUIRE UN TEL DISPOSITIF

Publication

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Application

EP 05774386 A 20050813

Priority

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Abstract (en)

[origin: WO2006032230A1] The invention relates to a method for producing a device for gas separation, said device comprising a layer system wherein a functional layer consisting of TiO₂ and/or ZrO₂ having an average pore diameter of less than 1 nm is applied to at least one side of a carrier layer that is porous throughout. Said carrier layer is preferably between 100 µm and 1 mm thick and comprises continuous pores with an average pore diameter in the µm range. The functional layer which is applied directly or by means of at least one intermediate layer comprises continuous pores with an average pore diameter of less than 1 nm, especially less than 0.8 nm. The functional layer can advantageously be embodied as a graduated layer. The invention is especially characterised by the symmetrical structure of the device, in which functional layers are applied to both sides of the carrier layer, optionally by means of respectively at least one intermediate layer.

IPC 8 full level

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Citation (search report)

See references of WO 2006032230A1

Citation (examination)

- US 4935139 A 19900619 - DAVIDSON ALEXANDER P [GB], et al
- WO 2005023403 A1 20050317 - KOREA RES INST CHEM TECH [KR], et al

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